



Sheet 1 of 2

<p>US Dept. of Commerce PATENT & TRADEMARK OFFICE</p> <p>INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)</p>		ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130
		APPLICANT Takahiro KISHIOKA	
		FILING DATE September 29, 2005	GROUP 1756

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Date	Name
CH	1	US 5,919,599	7/6/1999	Meador et al.
CH	2	US 5,693,691	12/2/1997	Flair et al.
CH	3	US 6,114,085	9/5/2000	Padmanaban et al.
CH	4	US 6,388,039 B1	5/14/2002	Jung et al.
CH	5	US 6,492,092 B1	12/10/2002	Foster et al.
CH	6	US 2002/0093069 A1	7/18/2002	Hong et al.
CH	7	US 2002/0127789 A1	9/12/2002	Hong et al.
CH	8	US 2002/0009595 A1	1/24/2002	Hong et al.

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation
CH	9	JP A 2000-294504	10/20/2000	Japan	X	X
CH	10	JP A 2002-47430	2/12/2002	Japan	X	X
CH	11	JP A 2002-190519	7/5/2002	Japan	X	X
CH	12	WO 02/05035 A1	1/17/2002	WIPO	X	
CH	13	JP A 2002-128847	5/9/2002	Japan	X	X
CH	14	JA A 11-279523	10/12/1999	Japan	X	X
CH	15	WO 02/086624 A1	10/31/2002	WIPO	X	
CH	16	JP A 2002-530696	9/17/2002	Japan	X	X
CH	17	JP A 2001-49231	2/20/2001	Japan	X	X
CH	18	JP A 2002-539282	11/19/2002	Japan	X	X
CH	19	JP A 10-333336	12/18/1998	Japan	X	X
CH	20	JP A 2002-105137	4/10/2002	Japan	X	X
CH	21	JP A 6-35201	2/10/1994	Japan	X	X
CH	22	JP A 2002-97231	4/2/2002	Japan	X	X
CH	23	JP A 2001-194799	7/19/2001	Japan	X	X
CH	24	JP A 10-120939	5/12/1998	Japan	X	X
CH	25	JP A 6-118656	4/28/1994	Japan	X	X

Date: May 11, 2006

Primary Examiner Cynthia Hamilton

09/21/2006



Sheet 2 of 2

Form PTO-1449 (REV. 1/06) US Dept. of Commerce PATENT & TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)			ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130
			APPLICANT Takahiro KISHIOKA	
			FILING DATE September 29, 2005	GROUP 1756
OTHER DOCUMENTS				
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)		
CH	26	Lynch et al.; "Properties and Performance of Near UV Reflectivity Control Layers;" Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229.		
CH	27	Taylor et al.; "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography;" Proceedings of SPIE, March 1999, Vol. 3678, pp. 174-185.		
CH	28	Meador et al.; "Recent Progress in 193 nm Antireflective Coatings;" Proceedings of SPIE, March 1999, Vol 3678, pp. 800-809.		
EXAMINER /Primary Examiner Cynthia Hamilton/			DATE CONSIDERED 09/21/2006	
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.				

9/21/2006

Date: May 11, 2006